

Integrated Half-Bridge Switch Using 70- μm -Thin Devices and Hollow Interconnects

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Abstract—An application-oriented integration concept for a half-bridge switch assembly has been developed based on the latest generation 70- μm -thin insulated gate bipolar transistors and diodes, which are rated at 600 V/200 A. This paper addresses the design and reliability of the assembly, with a fully bondwireless approach using cylindrical copper bumps. Advanced numerical structural simulation techniques are also applied to assess the influence of interconnect characteristics (material, size, and shape) and try to determine an optimum solution for reducing the stress and creep strain development in the solder joint. Preliminary experimental tests of the power module are also carried out at different switching frequency and loads to prove the validity of the proposed solution in terms of electromagnetic performance.

Index Terms—Copper bump, flip-chip, power electronics packaging, aging, solder joint, thermomechanical stress.

I. INTRODUCTION

THIS paper addresses the reliable integration of a half-bridge switch (HBS) based on last generation 70- μm -thin 600-V/200-A insulated-gate bipolar transistors (IGBTs) and diodes; in particular, it advances the state of the art as regards a recently presented packaging concept, which targets the optimization from an application point of view [1]. In the application, two transistors with antiparallel diodes need to be connected in series (high-side and low-side switch) to build a half-bridge power switch (HBS) configuration, as extensively required, for instance, by synchronous rectified dc-dc converters and by dc-ac converters (i.e., inverters). During operation within such power converter topologies, load current commutations always take place between high-side transistor and low-side diode (Cell-P) and, vice versa, between low-side transistor and high-side diode (Cell-N). Current commutation between antiparallel transistor-diode pairs only takes place at zero voltage in the case of synchronous rectified dc-dc converters, and at zero current in the case of inverters, and is thus, by definition, noncritical in both cases (i.e., it does not imply power dissipation or potentially destructive voltage

overshoots). Therefore, as pointed out in [2] and illustrated in Fig. 1, for improved switching performance, packaging design should aim at integrating and minimizing not the high-side or low-side basic switches, but rather the *positive* and *negative* switching cells, i.e., the high-side transistor/low-side diode and the low-side transistor/high-side diode pairs, respectively (the terminology positive and negative cell is derived from the sign of the load current during inverter operation). Based on these considerations, this paper presents an advanced and application-driven integration approach of a half-bridge power switch. In particular, in trying to optimize the switching and thermal performance of the HBS, the assembly is designed to construct with post (*power bump*) bondwireless sandwich packaging technology, which enables high power density levels, with double-sided cooling and reduced stray inductance. In the preliminary test, bondwires are still used here only for the transistor drive interconnection (i.e., gate and emitter) to use the existing substrate at this stage. However, the power and drive loops are clearly separated, and the driving loops are kept very small.

The use of thin devices in the switch implementation offers not only superior electrical but also thermal performance, as compared with thicker ones, and brings along increased power density figures [3]. Consequently, here, the main focus is on developing interconnect solutions, which can improve the thermomechanical performance of the assembled switch during fabrication and operation, preventing the benefits of thin device technology from being penalized at the packaging level.

II. SWITCH ASSEMBLY

The devices used for the switch assemblies are shown in Fig. 1: $10 \times 9.5 \times 0.07 \text{ mm}^3$ IGBTs and $9.5 \times 5.5 \times 0.07 \text{ mm}^3$ diodes, where the top metallization is treated with NiP/Ag finish being solderable. To achieve optimum performance in the application, packaging needs to target the integration of the positive and negative cells in the HBS (see Fig. 1); this can be achieved by having the devices in the same cell soldered on separate substrates, which are then mounted, one on top of the other, by means of interconnect posts (bumps), as shown in Fig. 2. This results in a low stray inductance and double-sided cooled power switch, where all devices have their backside in direct contact with a cooling surface [1]. Here, both the top and bottom substrates are direct bonded copper (DBC) consisting of a 1-mm-thick aluminum nitride tile sandwiched by 0.3-mm-thick copper on both sides.

The chips are soldered to the DBC substrates with 0.1-mm-thick Sn-3.5Ag solder alloy. The bumps are Cu with an outside

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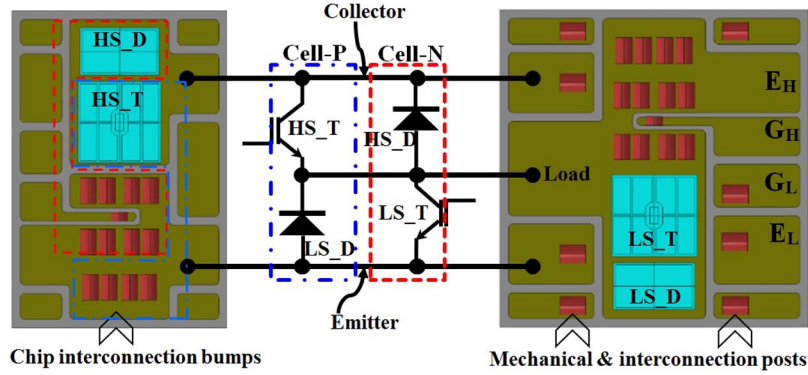


Fig. 1. Schematic of half-bridge power switch and the corresponding structural view.

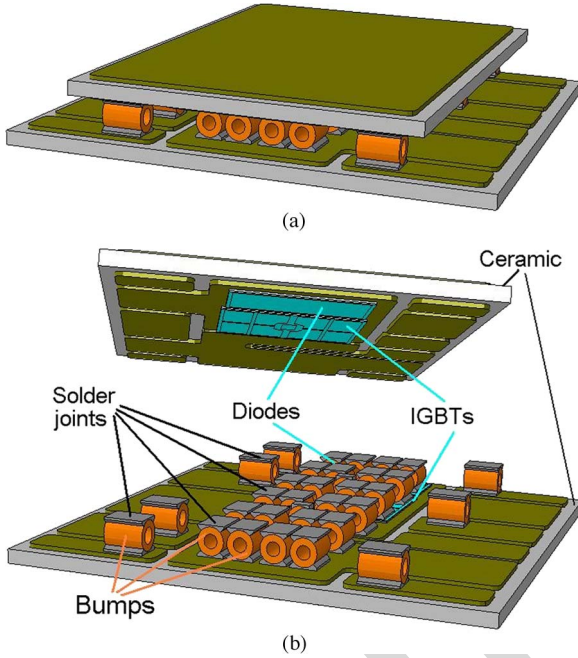


Fig. 2. Stacked assembly of substrate-chip-bump-substrate for the HBS. (a) Overall view. (b) Open view.

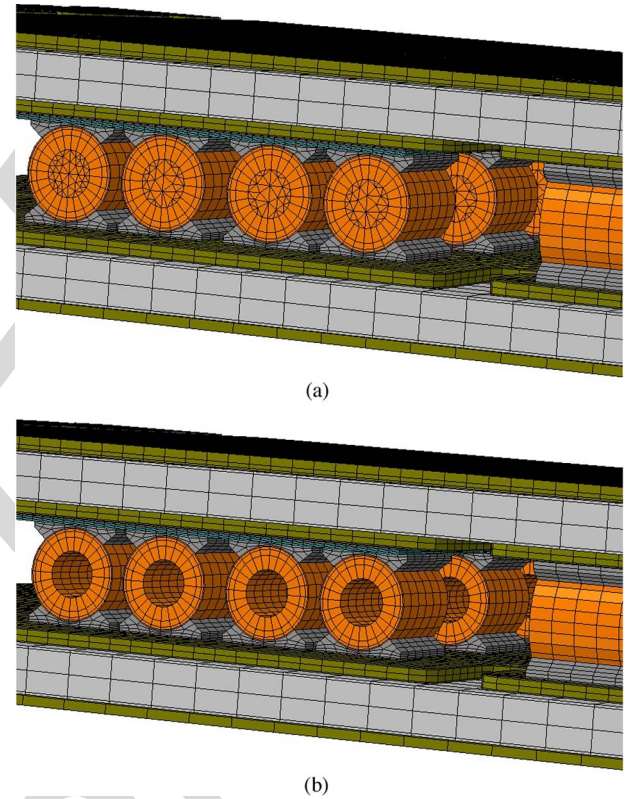


Fig. 3. Meshing systems used to discretize the assemblies with (a) solid bumps and (b) 0.5-mm-thick hollow bumps.

86 diameter of 2 mm and length of 3 mm. They are soldered
 87 to the front sides of the chips with Sn-3.5Ag solder of 0.1–
 88 0.4 mm in thickness, following the shape of the bumps. Due to
 89 the reduced thickness of the devices in this case, it is important
 90 to understand the effects of different interconnection geome-
 91 tries, sizes, materials, and shapes to yield optimum reliability.
 92 In particular, we report on a comparison of five hollow cylinder
 93 (0.5, 0.375, 0.25, 0.125, and 0.0625 mm in wall thickness)
 94 copper bumps with solid ones as the interconnect solution (see
 95 Fig. 3).

96

III. FE MODELING AND SIMULATION

97 The developed switch model was characterized electromag-
 98 netically and electrothermally, employing structural numerical
 99 analysis tools [13], and tested for functional performance.
 100 Fig. 4(a) shows the 3-D model mesh for the electromagnetic
 101 characterization of the assembly, which was performed with
 102 FastHenry [14]. As for the model in Fig. 4, it has been assumed
 103 that the paths through the chips, solders, and bumps were

considered as $5 \times 5 \times 2 \text{ mm}^3$ copper filament cubes, which
 104 carry uniform current and are connected together as a block
 105 (i.e., two for diode and four for IGBT). The model also uses
 106 a copper conducting material with an electrical conductivity
 107 of 59–600–000 S/m. The extraction was taken on a single
 108 path, while the unnecessary paths were being excluded, so that
 109 they do not contribute to the measuring path. The values of
 110 parasitic inductance between all terminal pairs [collector (C),
 111 emitter (E), and load (L)] were extracted and provided very
 112 encouraging indications. For instance, the estimated parasitic
 113 inductance between collector and emitter was less than 7 nH
 114 above 10 kHz (see Fig. 4).
 115

The adhesions between the interfaces of the die and solder,
 116 and between copper bump and solder, are the most critical
 117 surfaces in the whole module because they are prone to failure
 118

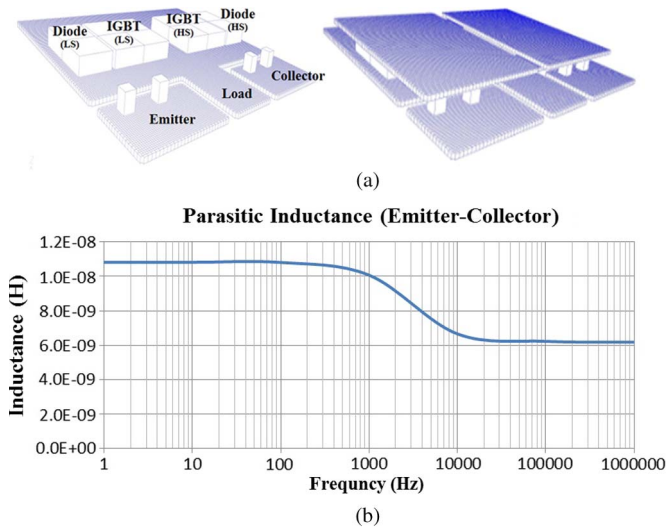


Fig. 4. (a) Three-dimensional model for electromagnetic characterization of the module; (b) extracted parasitic inductance.

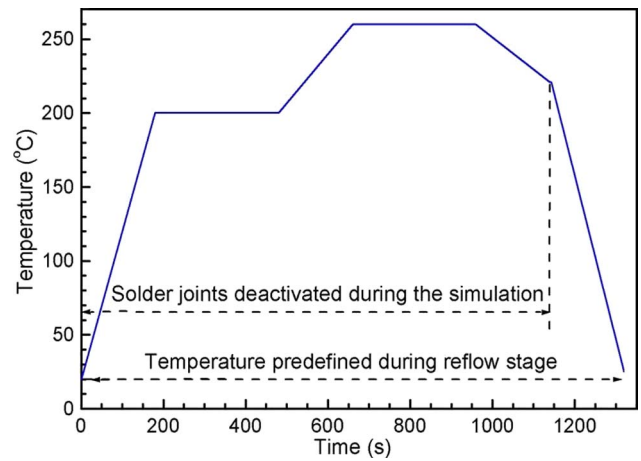


Fig. 5. Temperature profile representative of the reflow process.

119 with thermal cycling [4]. Finite element (FE) thermal and
 120 thermomechanical modeling and simulations have been carried
 121 out to compare the maximum junction temperature of the
 122 chips and the maximum residual stress/creep stain develop-
 123 ments in the solder joints in the three assemblies constructed
 124 using the three different bumps. The modeling and simulation
 125 were done using commercial FE analysis software ABAQUS
 126 6.10-2 and its graphic user interface Complete Abacus
 127 Environment. Fig. 3 presents an overview of the meshing
 128 systems consisting of 153–134 and 143–690 C3D8 and C3D6
 129 linear brick elements and triangular prism elements to discretize
 130 the assembly with solid and 0.5-mm-thick hollow cylinder
 131 bumps. Here, the largest element is $1 \times 1 \times 0.45 \text{ mm}^3$, and
 132 the smallest element is $0.5 \times 0.25 \times 0.025 \text{ mm}^3$. In addi-
 133 tion, S4 shell elements of $0.5 \text{ mm} \times 0.5 \text{ mm}$ or 0.5 mm
 134 $\times 0.25 \text{ mm}$, in size, were also used to discretize the NiP
 135 (nickel–phosphorus) finish on the surfaces of the substrates
 136 and the Al metallization on two sides of the chips and in-
 137 cluded in the thermomechanical modeling and simulation. For
 138 both diodes and IGBTs, the top side was treated with a gal-
 139 vanic process consisting of a $3.2 \mu\text{m}/500 \text{ nm}/300 \text{ nm}$ -thick
 140 AlSiCu/NiP/Pd solderable metallization, and the back side
 141 consists of a $1 \mu\text{m}/300 \text{ nm}/300 \text{ nm}$ -thick AlTi/Ni/Ag metal-
 142 lization. However, in the present model, they were assumed
 143 as a layer of $3.2\text{-}\mu\text{m}$ -thick Al on the top side and a layer of
 144 $1\text{-}\mu\text{m}$ -thick Al on the back side of the chips. This is based on the
 145 fact that most of the NiP/Pd and Ni/Ag layers would react with
 146 the liquid Sn–3.5Ag solder to form intermetallic compounds
 147 (IMCs) embedded within the matrix of the solder during the
 148 reflow process, and such IMCs were neglected.

149 As shown in Fig. 5, the assembly was first subjected to
 150 a predefined temperature profile to simulate the stress and
 151 strain development during the reflow process. In this stage, all
 152 the solder joints were deactivated, and thus, strain/stress did
 153 not develop in them until solidification of the molten solder
 154 occurred. Then, power losses of the IGBTs and diodes (see
 155 Fig. 6) were taken as heating sources to simulate the thermal
 156 performance of the assembly during a realistic mission pro-

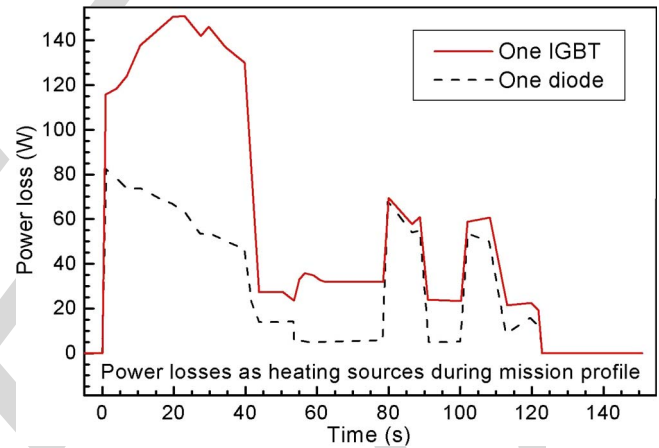


Fig. 6. Power losses of one IGBT and one diode during a mission profile derived from a real system operation.

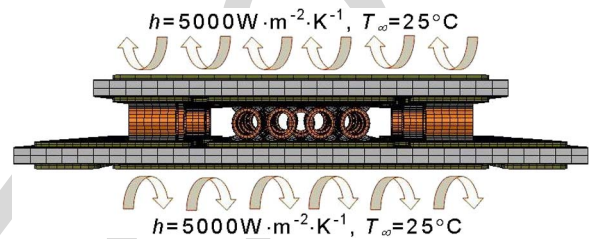


Fig. 7. Boundary condition of heat exchange applied in the thermal simulation during the mission profile.

file, and the heat exchange boundary condition, as described
 157 in Fig. 7, was applied to both the top and bottom cooling
 158 surfaces of the assembly. The heat exchange coefficient of
 159 $5000 \text{ W} \cdot \text{m}^{-2} \cdot \text{K}^{-1}$ is a typical value for using a forced-
 160 convection cooling in power electronics. The temperature field
 161 obtained from the thermal simulation was used as inputs to sim-
 162 ulate the further development of stress/strain in the assembly
 163 during the mission profile.

164 The thermal and mechanical properties of the Si, AlN ce-
 165 ramic tile, and NiP finish on the substrates for the thermal and
 166 thermomechanical simulations are listed in Table I [4]–[6]. For
 167 the rest of the materials in the assembly, Chaboche’s plastic
 168 model was used to describe the mechanical properties of the
 169

TABLE I
THERMAL AND MECHANICAL PROPERTIES OF Si, AlN CERAMIC LE, AND NiP FINISH

	Si	AlN	NiP
λ (W/(K·m))	146	175	...
C (J/(kg·°C))	750	740	...
ρ (kg/cm ³)	2.33	3.30	...
CTE (10 ⁻⁶ /K)	2.5	4.6	16.4
E (GPa)	130	331	60
ν	0.22	0.22	0.3

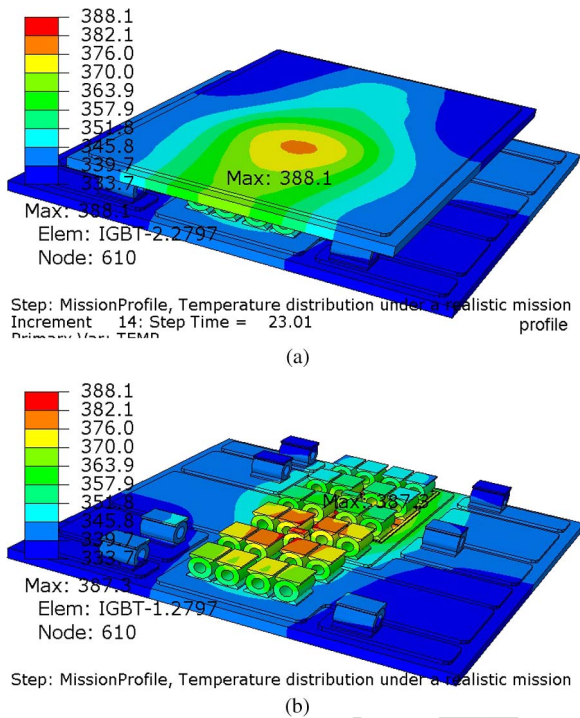


Fig. 8. Simulated results of temperature distribution in the assembly for 0.5-mm-thick hollow bumps: (a) whole assembly and (b) assembly with the top substrate removed.

170 Cu and Al, and Anand's creep model was used to describe
171 the mechanical properties of the Sn–3.5Ag solder alloy. All
172 the mechanical and thermal properties for the Cu, Al, and
173 Sn–3.5Ag were taken from [5] and [6] and are not repeated
174 here.

175 The simulation cases of the three assemblies with the three
176 different bumps were executed on a PC computer with an Intel
177 Pentium Core i7 CPU 976 at 3.20-GHz processor and 8-GB
178 RAM. The running times were about 50 h, for all the cases,
179 to simulate the thermomechanical residual stress/strain devel-
180 opments in the assemblies after the reflow process followed by
181 six cycles of the mission profile.

182 From the simulation results, the highest junction temperature
183 was observed on the IGBT attached on the top substrate and
184 at 23.01 s during the mission profile. Figs. 8 and 9 present the
185 simulated results of temperature distribution in the assembly
186 constructed with the 0.5-mm-thick hollow bumps at 23.01 s
187 during a realistic mission profile, where the bottom chips and
188 substrate of the assembly are separated for observing the hottest
189 IGBT in Fig. 8. Such a result is readily understood because
190 the power loss by an IGBT was higher than a diode, and

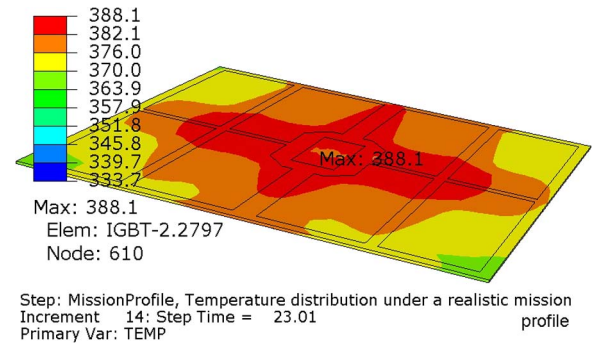


Fig. 9. Simulated temperature distributions in the hottest IGBT of the assembly during the mission profile for 0.5-mm-thick hollow bumps.

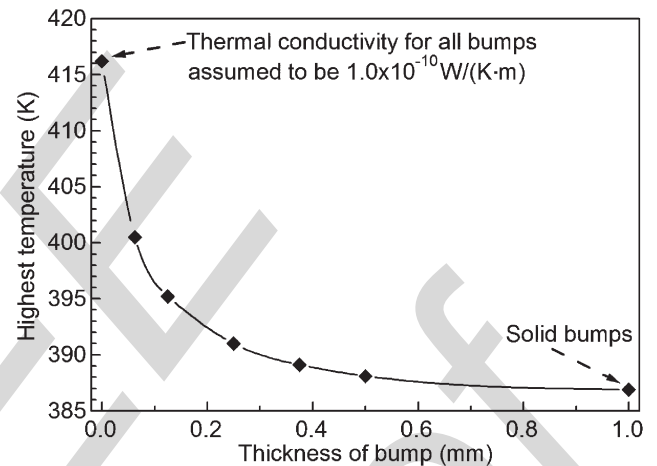
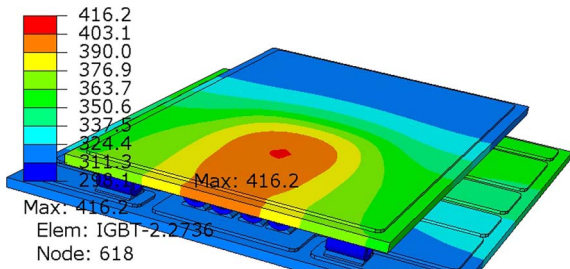


Fig. 10. Dependence of the simulated highest temperature in the assembly on the wall thickness of the bumps.

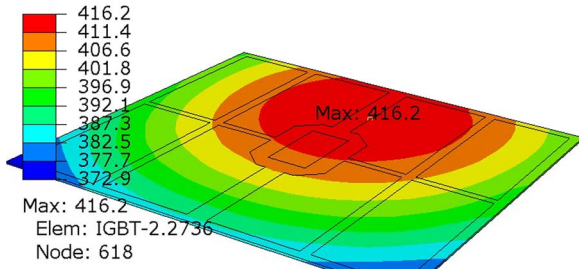
the cooling surface of the top substrate was slightly smaller 191
than the bottom substrate. The simulated results of temperature 192
distribution in the assembly constructed with the other five 193
types of bumps were similar, but the highest temperature in the 194
hottest IGBT depended on the wall thickness of the bumps (see 195
Fig. 10). The highest temperatures in the assembly constructed 196
with the six types of bumps increased with decreasing the wall 197
thickness of the bumps, and were 16.2 °C–29.3 °C lower than 198
the highest temperature in the assembly where the bumps were 199
assumed to have an extremely low thermal conductivity of 200
 1.0×10^{-10} W/(K·m). In all the six cases with real bumps, 201
the highest temperature location is at the center of the IGBT. In 202
the case where the bumps were assumed to have extremely low 203
thermal conductivity, the highest temperature location is still at 204
the same IGBT, but has been moved to one side (see Fig. 11). 205

206
During both reflow process and switch performance over six 207
cycles of the realistic mission profile, the FE thermomechanical 208
simulation results indicate that one of the solder joints between 209
the bumps and the chips has the highest thermomechanical 210
stress and creep strain accumulation among all the solder joints. 211
The maximum von Mises stress and creep strain accumulations 212
are at the corners of the solder layer in contact with the emitter 213
metallization of the IGBT, which are the most critical areas 214
of failure. Such a result can be attributed to the mismatch 215
of thermal expansion between the Sn–3.5Ag solder and the 216



Step: MissionProfile, Temperature distribution under a realistic mission profile
Increment 14; Step Time = 23.01
Primary Var: TEMP

(a)



Step: MissionProfile, Temperature distribution under a realistic mission profile
Increment 14; Step Time = 23.01
Primary Var: TEMP

(b)

Fig. 11. Simulated results of temperature distribution in the assembly for the bumps assumed to have an extremely low thermal conductivity of $1.0 \times 10^{-10} \text{ W}/(\text{K} \cdot \text{m})$: (a) whole assembly and (b) the hottest IGBT.

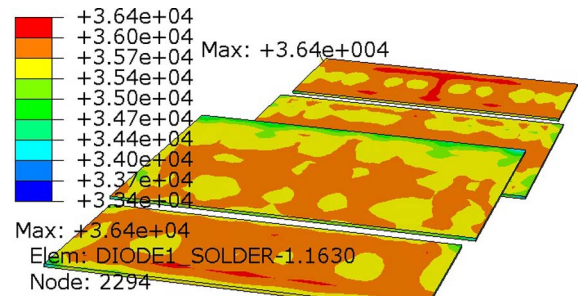


Step: T25, Cool down to 25C
Increment 24; Step Time = 180.0
Primary Var: S, Mises

Fig. 12. Simulated result of distribution of von Mises stress in the solder joints for the die attachment after a reflow process.

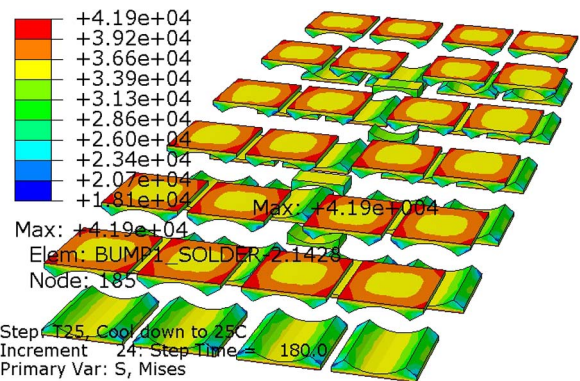
217 Si chips. Furthermore, it is also related to the joining area 218 or the shapes and size of the bumps. This can be seen from 219 the representative simulated results of the assembly with the 220 0.5-mm-thick bumps, as shown in Figs. 12–19. In Figs. 14, 15, 221 18, and 19, the first and last rows of four bump solders are for 222 the two diodes, and the center four rows of bump solders are for 223 the two IGBTs.

224 Figs. 20–23 compare the simulated maximum residual von 225 Mises stress and creep strain accumulation in the solder joints 226 for the die attachment and bump interconnects between the 227 assemblies with the six different bumps. In comparison with the 228 solid bumps, the hollow bumps can reduce the residual stress 229 in the as-reflowed solder joint both for the die attachment and 230 for the bump interconnects (see Figs. 20 and 21). It is noted 231 that the maximum residual stresses in the solder joints for the



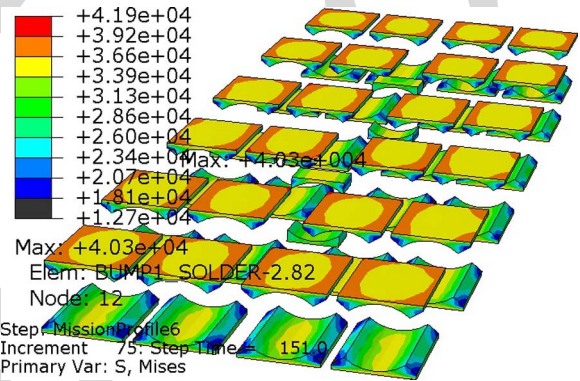
Step: MissionProfile6
Increment 75; Step Time = 151.0
Primary Var: S, Mises

Fig. 13. Simulated distribution of von Mises stress in the solder joints for the die attachment after six cycles of the mission profile.



Step: T25, Cool down to 25C
Increment 24; Step Time = 180.0
Primary Var: S, Mises

Fig. 14. Simulated distribution of von Mises stress in the solder joints for bump interconnects after the reflow process.



Step: MissionProfile6
Increment 75; Step Time = 151.0
Primary Var: S, Mises

Fig. 15. Simulated distribution of von Mises stress in the solder joints for bump interconnects after six cycles of the mission profile.

bump interconnects decrease with decreasing the wall thickness 232 of the bumps. This is readily understood because bumps with 233 thinner walls can be the bumps to be more compliant. As a 234 result, the more compliant bumps can withstand more elastic 235 deformation, and the solder joints and Si dice need relatively 236 low stress development against the mismatch coefficients of 237 thermal expansion and the different deformations. However, the 238 maximum residual von Mises stress in the solder joints for the 239 die attachment in the assembly with the 0.5-mm-thick bumps is 240 slightly lower than those in the assemblies with the other hollow 241 bumps. This may be attributed to the nonlinear stress–strain 242 relationship for the creep of the solder alloy. This is because 243

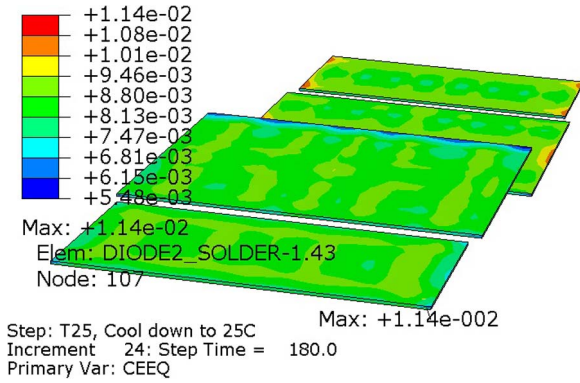


Fig. 16. Simulated distribution of creep strain accumulation in the solder joints for the die attachment after the reflow process.

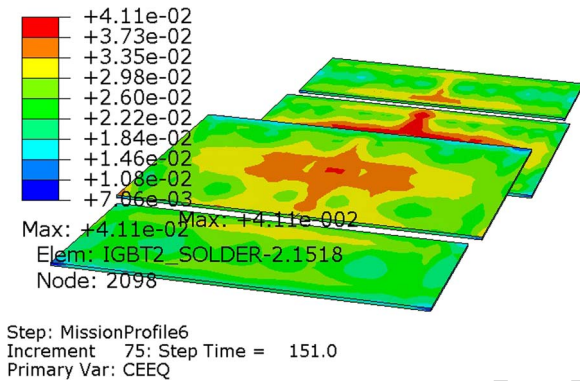


Fig. 17. Simulated distribution of creep strain accumulation in the solder joints for the die attachment after six cycles of the mission profile.

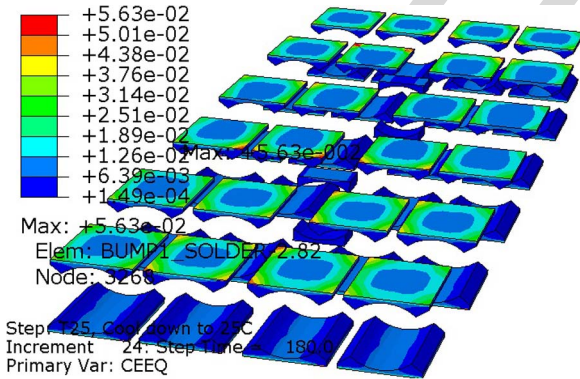


Fig. 18. Simulated distribution of creep strain accumulation in the solder joints for bump interconnects after the reflow process.

244 a higher stress may lead to a higher creep deformation, while a
 245 higher creep deformation may result in a larger stress release.
 246 During the cooling stage of the reflow, the solder joints for the
 247 die attachment in the assembly with the 0.5-mm-thick bumps
 248 were probably experienced with relatively large stress release.
 249 Therefore, the maximum residual von Mises stress in the solder
 250 joints for the bump interconnects still decrease.

251 After some stress release during the first cycle of the mission
 252 profile, the maximum residual von Mises stress in the solder
 253 joints for the die attachment is almost the same for the six
 254 different bumps. The stress release in the assembly with the
 255 0.5-mm-thick bumps is negligible, and the stress release in

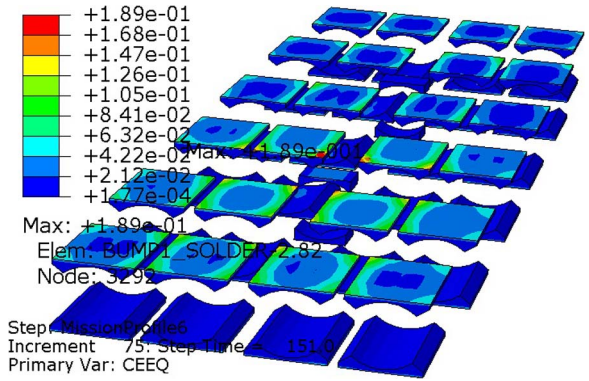


Fig. 19. Simulated distribution of creep strain accumulation in the solder joints for bump interconnects after six cycles of the mission profile.

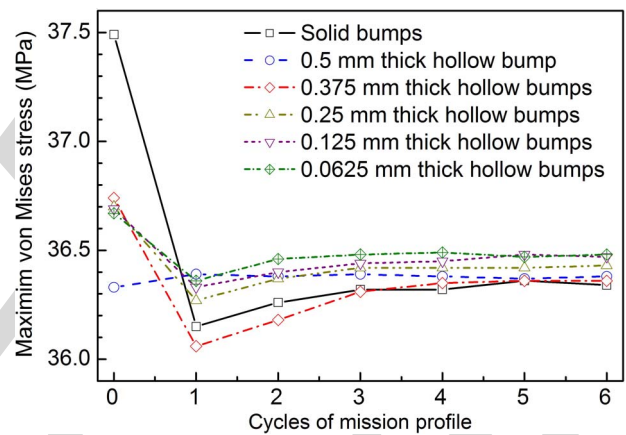


Fig. 20. Evolution of the simulated maximum residual von Mises stress in the solder joints for the die attachment, with respect to cycles of the mission profile.

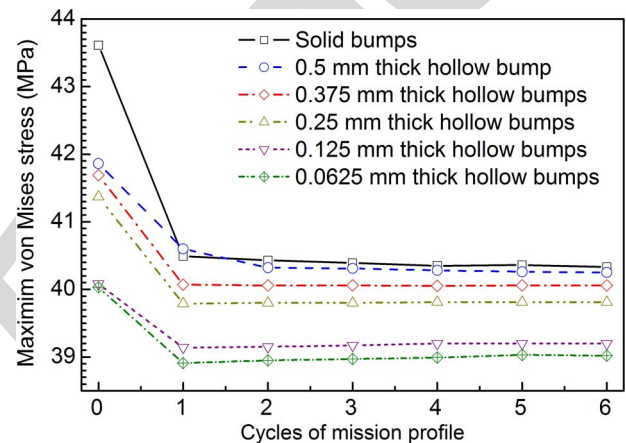


Fig. 21. Evolution of the simulated maximum residual von Mises stress in the solder joints for bump interconnects, with respect to cycles of the mission profile.

the assembly with the solid bumps is the largest. After the
 256 stress release during the first cycle of the mission profile, the
 257 maximum residual von Mises stress in the solder joints for
 258 the bump interconnects still decrease with decreasing the wall
 259 thickness of the bumps. Again, this can be explained with the
 260 increased compliance with decreasing the wall thickness of the
 261 bumps. Indeed, the difference of the maximum residual von
 262

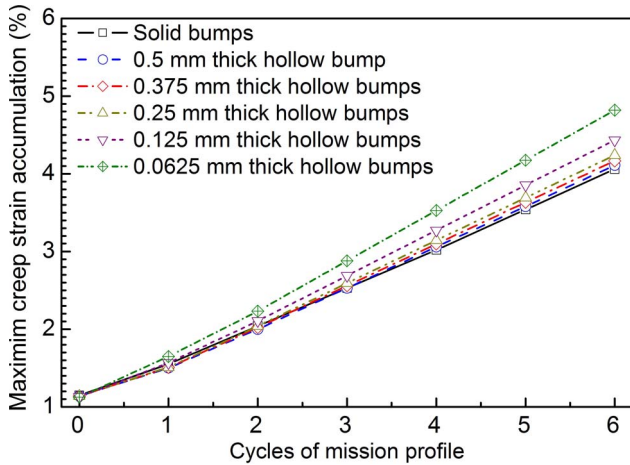


Fig. 22. Evolution of the simulated maximum creep strain accumulation in the solder joints for the die attachment, with respect to cycles of the mission profile.

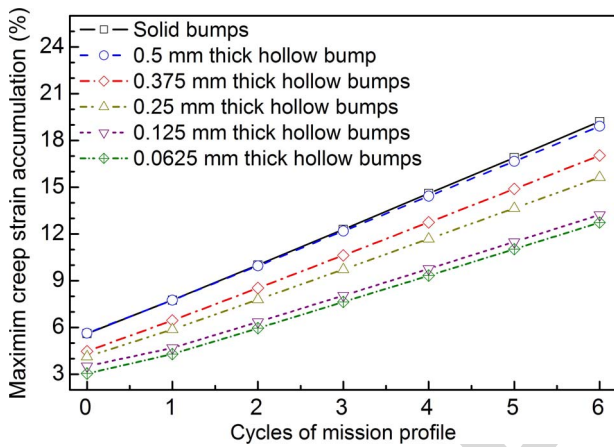


Fig. 23. Evolution of the simulated maximum creep strain accumulation in the solder joints for bump interconnects, with respect to cycles of the mission profile.

263 Mises stress in the solder joints in the assemblies with the
264 different bumps is quite low. This is due to the fact that there
265 was stress saturation during the creep deformation.

266 In response to the stress release during the first cycle of the
267 mission profile (see Figs. 20 and 21), the maximum creep strain
268 accumulations in the solder joints for both the die attachment
269 and the bump interconnects over this cycle are somewhat lower
270 than those over the other five cycles of the mission profile,
271 which are almost constants (see Figs. 22 and 23). Among
272 the six assemblies with the six different bumps, the overall
273 maximum creep strain accumulations in the solder joints for
274 the die attachment, with respect to cycles of the mission profile,
275 slightly increase with a decrease in the wall thickness of the
276 bumps. This can be attributed to the fact that the solder joints
277 in the assembly with thinner hollow bumps were subjected to
278 higher temperatures (see Figs. 8 and 10), and the solder alloy
279 has lower creep resistance at higher temperatures. However,
280 the maximum creep strain accumulation in the solder joints
281 for the bump interconnects clearly decrease with a decrease
282 in the wall thickness of the bumps. The 0.5-mm-thick bumps
283 can slightly reduce, and the 0.0625-mm-thick bumps can sig-

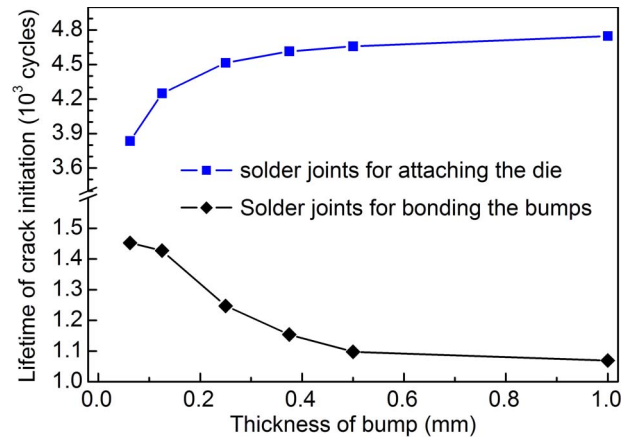


Fig. 24. Lifetimes predicted from the simulated maximum creep strain accumulation per cycle for the initiation of fatigue cracks in the solder joints.

nificantly reduce the maximum creep strain accumulation in 284
the solder joints for the bump interconnects when compared to 285
that for the solid bumps. Such a result reveals that the increase 286
in the compliance of the bumps through reduction in the wall 287
thickness is more effective than reducing the temperatures 288
through an increase in the wall thickness to reduce the creep 289
strain accumulation in the solder joints. 290

From the point of view of structural reliability, the reliability 291
of the solder joints can be assessed with the creep strain range, 292
accumulation, and energy density [5], [8], [9]. In the present 293
work, we employ the lifetime model of the SnAgCu solder 294
joints based on the creep strain accumulation [9], as follows: 295

$$N_f = \frac{1}{0.0405 \Delta \varepsilon_{cr}} \quad (1)$$

where N_f is the lifetime in number of cycles, and $\Delta \varepsilon_{cr}$ is 296
the creep strain accumulation per cycle. This is because the 297
eutectic Sn-3.5Ag solder alloy used to join the present Cu 298
bumps should be saturated with Cu during the reflow process. 299
Applying (1) to the maximum creep strain accumulations per 300
cycle, which were calculated in Figs. 22 and 23, the predicted 301
lifetimes are presented in Fig. 24. It can be seen that thinner 302
bumps can effectively improve the reliability of the assembly. 303
The maximum creep strain accumulations per cycle in all the 304
solder joints have been used, and thus, the predicted lifetimes 305
are better considered as the cycles of the mission profile, at 306
which fatigue cracks are initiated in the solder joints. They 307
can be used to compare the different bumps and optimize the 308
design. The lifetimes corresponding to the complete failure of 309
the solder joints should be longer than these predictions. 310

It is difficult to manufacture the hollow bumps with a wall 311
thickness thinner than 0.0625 mm. Based on the aforemen- 312
tioned simulation results, the 0.0625- and 0.125-mm-thick hol- 313
low bumps lead to an increase of 8.3 °C and 13.6 °C for the 314
highest temperature in the hottest IGBT, but ~35% longer for 315
the lifetime of the solder joints for the bump interconnects than 316
the solid bumps. Therefore, it is reasonable to select a wall 317
thickness of the bumps between 0.0625 and 0.125 mm. 318

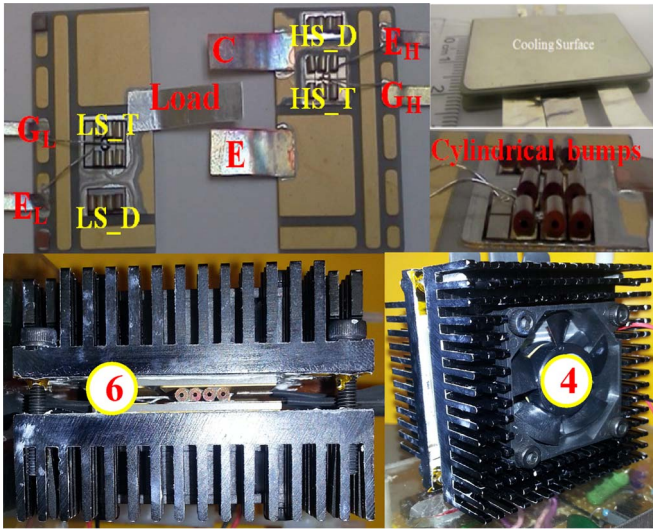


Fig. 25. Structure of half-bridge prototype (HBS).

319 IV. SWITCH PROTOTYPE AND PRELIMINARY 320 FUNCTIONAL TESTING

321 An initial prototype was constructed with the AlN-based
322 substrate available in our laboratory. First the transistor and
323 diode chips are soldered underside (collector and cathode)
324 onto a DBC substrate with a 100- μm -thick Sn-3.5Ag preform
325 that is employed in a fluxless reflow soldering process at a
326 peak temperature of 260 $^{\circ}\text{C}$ for 5 min. Ultrasonically bonded
327 375- μm -thick aluminum wires are used to create the gate and
328 emitter interconnections needed to drive the IGBT. These wires
329 are not power connections but only driving signals. Then, the
330 cylindrical copper bumps are soldered onto the chips using the
331 62Sn36Pb2Ag solder paste reflowed at a peak temperature of
332 240 $^{\circ}\text{C}$ for 5 min. Finally, the two substrates shown in Fig. 25
333 are positioned, one on top of the other, and soldered using
334 the 62Sn36Pd2Ag solder paste at a temperature of 260 $^{\circ}\text{C}$
335 for 5 min.

336 The functionality of the prototype was tested in a basic half-
337 bridge dc-ac converter, which can be implemented on typical
338 working conditions of multilevel converters. Fig. 25 shows the
339 structure of the HBS topology, where the top view of the HBS
340 structural halves with the indication of the electrical terminals
341 of HS_D and HS_T, corresponding to the high-side diode and
342 transistor, respectively; LS_D and LS_T relate to the low-side
343 diode and transistor, respectively. E_H, G_H, and E_L, G_L are the
344 high- and low-side emitter and gate terminals, respectively.

345 Fig. 26 illustrates the fully integrated prototype assembly,
346 containing two heatsinks, fans, dc-link capacitors, and resistors
347 mounted all together, such that the gate drive is connected at
348 the bottom and the dc-link capacitors and resistors to the top
349 part of the power module. This configuration will not only
350 isolate the gate signals to/from the power circuit but also reduce
351 the external loop inductance of the wires connected to the
352 module where the dc-link capacitors and the gate signals are
353 very close to the devices. The test conditions were set, as
354 depicted in Table II. A fixed dead time of 0.9 μs was chosen,
355 and the inverter is tested in an open-loop system. Two identical
356 heatsinks, each embedded with a 12-V fan, were attached to

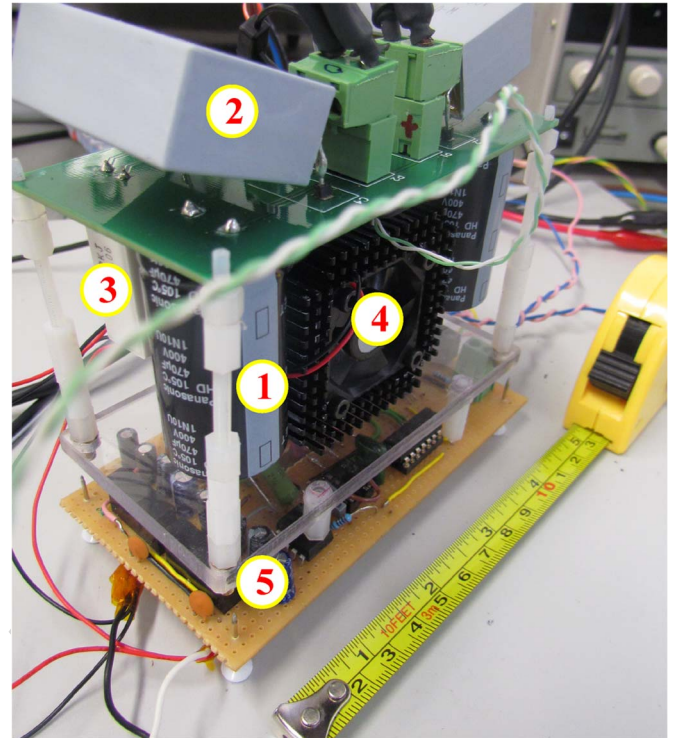


Fig. 26. Half-bridge power module.

TABLE II
DESIGN PARAMETERS OF THE POWER MODULE

Input voltage		400V
Switching frequencies		10KHz, 15KHz & 20KHz
Dead-Time		900ns
Load resistors		19.2 Ω , 28.8 Ω & 38.4 Ω
Load inductor		5mH
①	C3 and C4	470 μF (electrolytic)
②	C1 and C2	4.7 μF (Film)
③	R1 and R2	22K Ω
④ Heatsink embedded with 12V fan		
⑤ Gate drive circuit		
⑥ Device under test (HBS)		

both cooling surfaces of the switch, in order to cool down the
357 module at high power rating while providing space exploitation
358 to the overall size of the power cell. 359

The gate drive circuit and the power side interconnections
360 are kept very close to the power converter, in order to reduce the
361 noise pickup at the gate signals and parasitic inductances. As for
362 the schematic diagram (see Fig. 27), the input is center tapped
363 with dc-link capacitors. This kind of configuration requires
364 a very large capacitor value to decrease the low-frequency
365 voltage oscillation at the capacitor midpoint. Here, both elec-
366 trolytic and high-frequency capacitors are used to suppress the
367 voltage oscillation at the dc bus. For the gate signal, a basic
368 pulsewidth modulation strategy is used, where the carrier and
369 modulating signals are taken from external signal generators
370 and are properly processed inside the gate drive to provide
371 the required sequence. Both Gate_H and Gate_L drive signals
372 are passed through isolation, deadtime, and current boosting
373 circuitry to prevent shoot through and enable high-frequency
374 operation of the power transistors. The heatsink was equipped 375

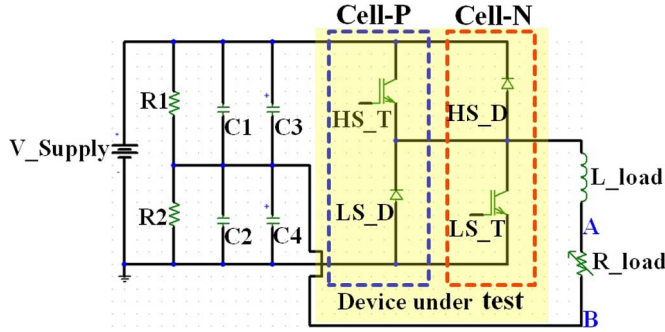


Fig. 27. Schematic of HBS test-circuit.

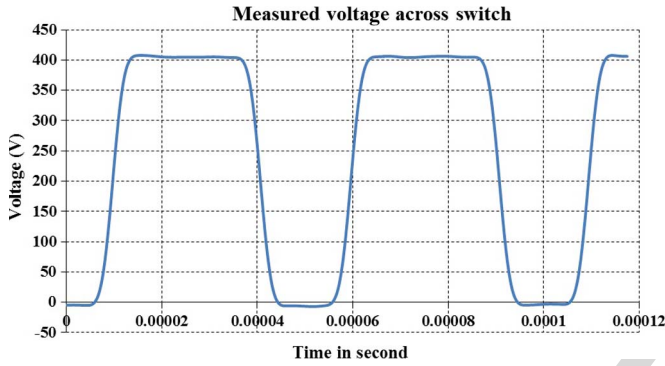


Fig. 28. Experimental result: collector–emitter voltage.

376 with a thermocouple on the device side closer to the IGBT,
 377 so that the average heatsink and device temperature can be
 378 estimated.

379 Two LeCroy differential probes were placed across the
 380 high-side transistor and the load resistor of $19.2\ \Omega$, and the
 381 corresponding results were then observed using a LeCroy os-
 382 cilloscope. The representative experimental result shown in
 383 Fig. 28 is the voltage across the switch (V_{ce}), and the exper-
 384 imental result in Fig. 29 is the voltage across the load resistor
 385 (V_{AB}) and output current.

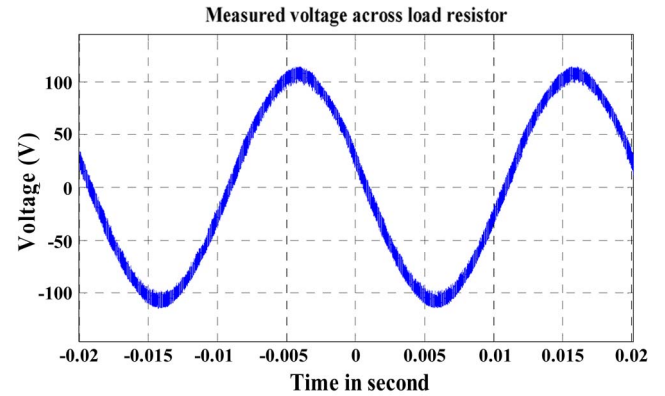
386 The test results shown in Figs. 28 and 29 were taken, and an
 387 average steady-state temperature of $70\ ^\circ\text{C}$ was recorded, while
 388 the switch was operating at 400-V input voltage, 12-V fan volt-
 389 age, and 20-kHz switching frequency. These results confirm the
 390 perfect functionality of the switch and, more importantly, reveal
 391 a very contained value of parasitic inductance, as shown in the
 392 graph depicted in Fig. 28. As for the result, it is clear that there
 393 is an absence of voltage overshoot across the switch during
 394 current commutation. In addition, the result also agrees with
 395 the reduced stray inductance extracted by the electromagnetic
 396 simulation.

397 The graph shown in Fig. 30 is the calculated efficiency of
 398 the converter, using the supply input and experimental results
 399 at three different frequencies, as follows:

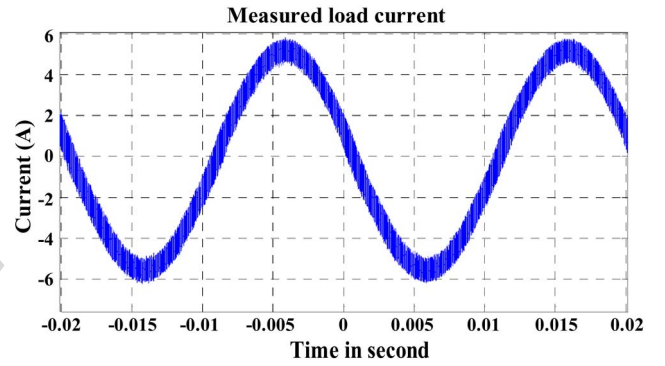
$$\eta = \frac{P_{\text{out}}}{P'_{\text{in}}} \times 100\% \quad (2)$$

$$P'_{\text{in}} = P_{\text{in}} - P_R \quad (3)$$

$$P_R = \frac{2 \left(\frac{V_{\text{in}}}{2} \right)^2}{R} \quad (4)$$



(a)



(b)

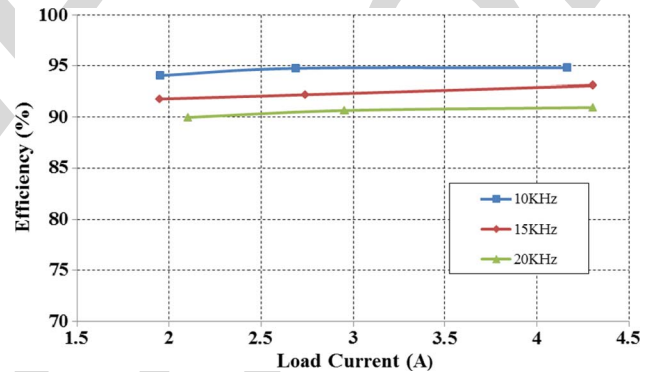
Fig. 29. Experimental result: output voltage (V_{AB}) across the (a) load resistor and (b) output current.

Fig. 30. Efficiency as a function of output current at different switching frequencies.

where
 P_{in} input power of the overall circuit;
 P_{out} output power;
 P'_{in} converter input power.

The total power consumed by the two resistors (R_1 and R_2)
 in Fig. 27) was evaluated using (4) and deducted from the
 measured input power (P_{in}), which is the power that entered
 into the converter. Then, the efficiency of the converter is
 calculated.

Looking from the efficiency graph, at the higher switching
 frequency of 20 kHz, it can be seen that the efficiencies
 are still above 90% at light and full loads. The efficiency at
 20 kHz is 4% lower than that of the 10-kHz switching frequency
 operation. However, a 20-kHz frequency operation can save

TABLE III
LOAD INDUCTOR COMPARISON

	10KHz	20KHz
	5mH	2.5mH
Output current ripple	0.531A	0.508A
Commercial device	£67.22 – for 2.5mH, £182.08 – for 5mH,	

414 significant costs on the external passive components and make
415 for a smaller package, while reducing the output ripple current.
416 The price list shown in Table III indicates that using almost the
417 same output ripple current of 0.5 A, a 20-kHz switching fre-
418 quency operation can reduce the cost of the inductor by almost
419 three times, using 10-kHz frequency operation. In addition, it
420 is worth mentioning that the presented efficiency graph does
421 not include the power consumed by the driver circuit, and it
422 only includes the power semiconductor device losses, input
423 resistance losses, and output inductance losses.

424

V. CONCLUSION AND OUTLOOK

425 This paper has presented an advanced integration approach
426 for power device packaging, demonstrating the correct elec-
427 trical functionality of the half-bridge power switch and its
428 thermal performance. Solid bumps and thicker hollow bumps
429 have better thermal performance than thinner hollow bumps,
430 in terms of reducing the temperatures at the hottest IGBT.
431 However, thinner hollow bumps can reduce the creep strain
432 accumulation in the critical solder joints, as compared to the
433 solid bumps and thicker hollow bumps. As for the thermome-
434 chanical simulation results, the 0.0625-mm-thick bumps can
435 significantly reduce the maximum creep strain accumulation in
436 the solder joints for the bump interconnects. For this reason,
437 such results can effectively improve the reliability of the assem-
438 bly, and the approach can greatly enhance power density and
439 reduce stray inductance, while enabling double-sided cooling
440 capability. Preliminary experimental results show an interesting
441 advancement of the state of the art, which is represented by the
442 recently proposed sandwich package concepts based on solid
443 bump interconnections and double-sided cooling [10]–[12], in
444 particular by ensuring a more even temperature distribution
445 within the power module and by further reducing parasitic
446 inductance. For future work, it is anticipated to extend this
447 approach to a more advanced scheme while further reducing the
448 stray inductance, improving the reliability of such assemblies
449 and the ability to test with a direct substrate liquid cooling
450 system.

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cooling of power devices. 523

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